ONS00462 10/603,258

TO: USPTO

## IN THE CLAIMS

Please cancel claims 1-6.

7. (Original) A method for forming an electronic package comprising the steps of:

attaching an electronic chip to a support substrate, wherein the electronic chip includes a bond pad on an outer surface; attaching a conductive stud to the bond pad;

encapsulating the electronic chip to form a sub-assembly having an upper surface;

forming an opening in the upper surface to expose the conductive stud;

forming a barrier layer on the conductive stud; and attaching a solder bump to the barrier layer.

- 8. (Original) The method of claim 7 wherein the step of forming the barrier layer includes forming a nickel barrier layer.
- 9. (Original) The method of claim 7 wherein the step of forming the barrier layer comprises the steps of:

placing the sub-assembly in an electroless plating bath; and injecting plating solution towards the opening to form the barrier layer on the conductive stud.

- 10. (Original) The method of claim 9 further comprising the step of agitating the electroless plating bath.
- 11. (Original) The method of claim 9 wherein the step of placing the sub-assembly includes placing the sub-assembly in an electroless nickel plating solution.

ONS00462 10/603,258

- 12. (Original) The method of claim 9 further comprising the step of masking the support substrate.
- 13. (Original) The method of claim 7 wherein the step of attaching the conductive stud includes attaching a gold stud.
- 14. (Original) A method for forming a direct chip attach device comprising the steps of:

providing a sub-assembly comprising a lead frame, a chip attached the lead frame, a bond pad formed on an outer surface of the chip, a conductive bump attached to the bond pad, and an encapsulating layer covering the chip, wherein the encapsulating layer has an opening to expose the conductive bump;

placing the sub-assembly in an electroless plating solution; and

injecting electroless plating solution towards the opening to form a barrier layer on the conductive bump.

- 15. (Original) The method of claim 14 further comprising the step of covering exposed portions of the lead frame with a masking layer.
- 16. (Original) The method of claim 14 wherein the step of placing the sub-assembly includes placing the sub-assembly in an electroless nickel plating bath.
- 17. (Original) The method of claim 14 further comprising the step of coupling a solder bump to the barrier layer.
- 18. (Original) The method of claim 14 further comprising the step of agitating the electroless plating solution.

Please cancel claims 19-20.

ONS00462 10/603,258

TO: USPTO

Please add the following new claims:

21. (New) A process for forming a direct chip attach device comprising the steps of:

providing the direct chip attach device including an encapsulated electronic chip having an opening to expose a first conductive portion coupled to the electronic chip;

forming a barrier layer on the first conductive portion; and attaching a second conductive portion to the barrier layer.

- 22. (New) The process of claim 21 wherein the step of providing the direct chip attach device includes providing an encapsulated power MOSFET device.
- 23. (New) The process of claim 21 wherein the step of providing the direct chip attach device includes providing the encapsulated electronic chip, wherein the encapsulated electronic chip is attached to a lead frame including an exposed flag, the process further including the steps of:

forming the barrier layer on the exposed flag; and attaching a third conductive portion to the barrier layer on the exposed flag.

- 24. (New) The process of claim 21 wherein the step of forming the barrier layer includes forming a barrier layer including nickel.
- 25. (New) The process of claim 21 wherein the step of forming the barrier layer comprises the steps of:

placing the sub-assembly in an electroless plating bath; and injecting plating solution towards the opening to form the barrier layer on the conductive stud.

JUL-06-2004 13:26 FROM:ON SEMI LAW

ONS00462 10/603,258

- 26. The process of claim 25 further comprising (New) the step of agitating the electroless plating bath.
- 27. (New) The process of claim 25 wherein the step of placing the sub-assembly includes placing the sub-assembly in an electroless nickel plating solution.
- 28. The process of claim 21 wherein the step of providing the direct chip attach device includes providing direct chip attach device wherein the first conductive portion comprises gold.